[WA1] Contamination Control in Semiconductor / Display Technologies	
Date / Time	July 25 (Wed.), 2018 / 09:00-10:00, 13:00-13:40
Place	Room A (#104~106)
Session Chair(s)	Taesung Kim (Sungkyunkwan Univ., Korea)

WA1-1 [Invited] **09:00-09:30**

Challenges of Particle Control Technology in the Semiconductor and Display Process Equipments

Seungki Chae
Sungkyunkwan Univ., Korea

WA1-2 [Invited] **09:30-10:00**

Towards Automation of Quantitative Analysis of Various Digital Images for Material and Process Characterization

Woo Sik Yoo
WaferMasters, Inc., USA

WA1-3 **13:00-13:20**

Characterization of Atmospheric Electrodeless Microwave Plasma in Nitrogen

Hojoong Sun, Jungwun Lee, and Moon Soo Bak
Sungkyunkwan Univ., Korea

WA1-4 **13:20-13:40**

Mechanism Analysis of NH_3/NF_3 Remote Plasma Dry Cleaning Reactions Using TOF-MASS

Jiheon Kim[1], Shin Kim[1], Kyoungwoo Kwon[1], Byeonghwa Jeong[1], Kiyoung Yun[1], Seoungki Chae[2], and Kyunghwan Jeong[2]
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